

Amendments to the Specification:

Please replace the heading on page 8, line 8, of the application as originally filed with the following amended heading:

PROBLEMS TO BE SOLVES SOLVED BY THE INVENTION

Please replace the paragraph beginning on page 9, line 18, and ending on page 9, line 25, of the application as originally filed with the following amended paragraph:

Referring to FIG. 5, it can be seen that the cleaning rate increases with increase in the NF₃ gas concentration in the Ar/NF₃ mixed gas. From this, it is derived that it is preferable to add NF₃ to the Ar/NF₃ mixed gas supplied to the remote plasma source 16C with the concentration (=Ar/(Ar+NF₃)) of at least 5%, in order to achieve the cleaning rate of 500 nm/minute nm/muinite or more under the pressure of 1200 Pa.